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Marjorie Scariati

IN THE UNITED STATES PATENT & TRADEMARK OFFICE

APPLICANT(S): David Mui et al.

SERIAL NO.: 09/905,172

FILING DATE: 07/13/01

TITLE: ETCH PATTERN DEFINITION USING A CVD ORGANIC LAYER AS AN
ANTI-REFLECTION COATING AND HARDMASK

ART UNIT: 1765

ATTY DOCKET: 6188 (OLD) / 004227 USA02/ETCH/SILICON/JB1 (NEW)

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Assistant Commissioner for Patents
Washington, DC 20231

LETTER REQUESTING CHANGE OF ATTORNEY DOCKET NUMBER

A Response to Notice to File Missing Parts is filed herewith.

The above application was filed on July 13, 2001, identified by attorney docket number 6188. It is respectfully requested that the attorney docket number on this application be changed to 004227 USA02/ETCH/SILICON/JB1. All documents included in the enclosed Response to Notice to File Missing Parts reflect the revised docket number, and it is requested that all future Patent Office communications be identified by the new docket number accordingly.

Respectfully submitted,

Robert W. Mulcahy Reg. No. 25,436

Date: _____

OATH & ASSIGNMENT

1. The undersigned hereby undertake that the invention/new utility model/new design entitled:

**Title: ETCH PATTERN DEFINITION USING A CVD ORGANIC LAYER AS AN ANTI-REFLECTION
COATING AND HARMASK**

was truly invented by me/us. The undersigned agree to accept punishments provided for in laws in case of any imposture, plagiarism, imitation or deceptive activities

2. The undersigned hereby assign all my/our rights and interests regarding the invention/new utility model/new design, including the right to claim priority, insofar as the Republic of China is concerned to: APPLIED MATERIALS, INC.

a corporation organized and existing under the laws of the State of Delaware, United States of America and located at 3050 Bowers Avenue, Santa Clara, California 95054, U.S.A.

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List of Reference Numbers

- 130 Material to be etched
- 140 CVD organic layer
- 150 Dielectric layer
- 160 Patterned photoresist layer
- 210 Silicon substrate
- 220 Gate oxide layer
- 230 Doped polycrystalline silicon layer
- 240 CVD organic layer
- 250 Silicon oxynitride layer
- 260 Patterned photoresist layer
- 310 Semiconductor substrate
- 320 Pad oxide layer
- 330 Silicon nitride layer
- 340 CVD organic layer
- 350 Silicon oxynitride layer
- 360 Patterned photoresist layer